L Number	Hits	Search Text	DB	Time stamp
1	110		USPAT;	2001/10/04 20:55
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
1		(material 4 - 1 - 1 - 1 - 1 - 1 - 1 - 1 - 1 - 1 -	IBM TDB	
2	44	()	USPAT;	2001/10/04 21:18
		silicon) and 257/\$5.ccls.	US-PGPUB;	
			EPO; JPO;	
			DERWENT; IBM TDB	
3	133	(tunnel near6 gate near6 (insulation or	USPAT;	2001/10/04 21:20
		insulating) adj film) and 257/\$5.ccls.	US-PGPUB;	2001/10/04 21.20
		, the same and the	EPO; JPO;	
			DERWENT;	
			IBM TDB	
4	1		USPAT;	2001/10/04 21:21
		insulating) adj film) and 257/\$5.ccls. and	US-PGPUB;	
		silicon adj oxynitride	EPO; JPO;	
			DERWENT;	
	1211	//#257/256#\ /#257/257#\ - /#257/250#\	IBM TDB	
	1211	(("257/356") or ("257/357") or ("257/359") or ("257/360")).CCLS.	USPAT;	2001/10/04 20:52
İ		OI (237/300)4.CCLS.	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM TDB	
-	1399	(("257/410") or ("257/411") or	USPAT;	2001/10/04 11:30
		("257/412")).CCLS.	US-PGPUB;	2001, 10, 01 11.00
		•	EPO; JPO;	
			DERWENT;	
			IBM TDB	
-	1078	(== :, == , == (== :, ==)	USPAT;	2001/10/04 11:31
		or ("257/639") or ("257/649")).CCLS.	US-PGPUB;	
			EPO; JPO;	
			DERWENT; IBM TDB	
_	3605	((("257/356") or ("257/357") or	USPAT;	2001/10/04 11:31
		("257/359") or ("257/360")).CCLS.) or	US-PGPUB;	2001/10/04 11.31
		((("257/410") or ("257/411") or	EPO; JPO;	
		("257/412")).CCLS.) or ((("257/632") or	DERWENT;	
		("257/635") or ("257/638") or ("257/639")	IBM TDB	Ì
		or ("257/649")).CCLS.)		
-	3139	(((("257/356") or ("257/357") or	USPAT;	2001/10/04 14:37
		("257/359") or ("257/360")).CCLS.) or	US-PGPUB;	
		((("257/410") or ("257/411") or ("257/412")).CCLS.) or ((("257/632") or	EPO; JPO;	
		("257/635") or ("257/638") or ("257/639")	DERWENT;	
		or ("257/649")).CCLS.)) and	IBM TDB	
		(@rlad<19990429 or @pd<19990428)		
-	594	((((("257/356") or ("257/357") or	USPAT;	2001/10/04 11:44
		("257/359") or ("257/360")).CCLS.) or	US-PGPUB;	
		((("257/410") or ("257/411") or	EPO; JPO;	
		("257/412")).CCLS.) or ((("257/632") or	DERWENT;	
		("257/635") or ("257/638") or ("257/639")	IBM TDB	
		or ("257/649")).CCLS.)) and (@rlad<19990429 or @pd<19990428)) and		
		(gate near10 (insulation or insulator or		
		isolation or isolator))		
	518	(((((("257/356") or ("257/357") or	USPAT;	2001/10/04 11:50
		("257/359") or ("257/360")).CCLS.) or	US-PGPUB;	2001, 10, 01 11.00
		((("257/410") or ("257/411") or	EPO; JPO;	
	ļ	("257/412")).CCLS.) or ((("257/632") or	DERWENT;	
		("257/635") or ("257/638") or ("257/639")	IBM TDB	
		or ("257/649")).CCLS.)) and		
		(@rlad<19990429 or @pd<19990428)) and		
		(gate near10 (insulation or insulator or		
	1	isolation or isolator))) and (silicon or polysilicon or polycrystalline near5		
		silicon)		
LL.		VVV++/		

		(4057/0578)	USPAT;	2001/10/04 11:52
-	377	((((((("257/356") or ("257/357") or ("257/359") or ("257/360")).CCLS.) or ((("257/410") or ("257/411") or	US-PGPUB; EPO; JPO;	2001/10/04 11.32
		("257/412")).CCLS.) or ((("257/632") or	DERWENT;	
		("257/635") or ("257/638") or ("257/639")	IBM TDB	
		or ("257/649")).CCLS.)) and		
		(@rlad<19990429 or @pd<19990428)) and (gate near10 (insulation or insulator or		
		isolation or isolator))) and (silicon or		
		polysilicon or polycrystalline near5		
		silicon)) and (doped or dopant or doping)	WODDE.	2001/10/04 11:55
-	241	((((((("257/356") or ("257/357") or	USPAT; US-PGPUB;	2001/10/04 11:33
		("257/359") or ("257/360")).CCLS.) or ((("257/410") or ("257/411") or	EPO; JPO;	,
		("257/412")).CCLS.) or ((("257/632") or	DERWENT;	
		("257/635") or ("257/638") or ("257/639")	IBM TDB	
		or ("257/649")).CCLS.)) and		
		(@rlad<19990429 or @pd<19990428)) and (gate near10 (insulation or insulator or		
		isolation or isolator))) and (silicon or		
		polysilicon or polycrystalline near5		
		silicon)) and (doped or dopant or doping))		
		and (oxygen or oxynitride or silicon adj dioxide)		
_	196	(((((((("257/356") or ("257/357") or	USPAT;	2001/10/04 13:44
	130	("257/359") or ("257/360")).CCLS.) or	US-PGPUB;	
		((("257/410") or ("257/411") or	EPO; JPO; DERWENT;	
		("257/412")).CCLS.) or ((("257/632") or ("257/635") or ("257/638") or ("257/639")	IBM TDB	
		or ("257/649")).CCLS.)) and	1511 155	
		(@rlad<19990429 or @pd<19990428)) and		
		(gate near10 (insulation or insulator or		
		isolation or isolator))) and (silicon or polysilicon or polycrystalline near5		
		silicon)) and (doped or dopant or doping))		
		and (oxygen or oxynitride or silicon adj		
		dioxide)) and (nitrogen or oxynitride or		
	100	nitride) (("6277708") or ("6236094") or ("6191462")	USPAT;	2001/10/04 13:46
-	100	or ("6163050") or ("6133602") or	US-PGPUB;	
		("6107657") or ("5962897") or ("5923056")	EPO; JPO;	
		or ("5886368") or ("5838051") or	DERWENT;	
		("5831319") or ("5828111") or ("5811865") or ("5710454") or ("5635746") or	IBM TDB	
		("5619051") or ("5614748") or ("5596214")		
		or ("5565691") or ("5412246") or		
		("5289030") or ("5276346") or ("5268590")		
		or ("5254867") or ("5237188") or ("5134451") or ("4954867") or ("4931411")		
		or ("4855247") or ("4814854") or		
		("4698787") or ("3913211") or ("3863330")		
		or ("3853633") or ("3724065")).PN.	Hanam.	2001/10/04 13:47
-	0	("L24 and silicon and oxygen and nitrogen and first.clm. and second.clm.").PN.	USPAT; US-PGPUB;	2001/10/04 13:47
		and first.cim. and second.cim.).fn.	EPO; JPO;	
			DERWENT;	
		•	IBM TDB	

			1	[0001/10/04 13.50]
[- [7	((("6277708") or ("6236094") or	USPAT;	2001/10/04 13:50
		("6191462") or ("6163050") or ("6133602")	US-PGPUB;	
		or ("6107657") or ("5962897") or	EPO; JPO; DERWENT;	
		("5923056") or ("5886368") or ("5838051")	IBM TDB	
]		or ("5831319") or ("5828111") or	IDM IDD	
		("5811865") or ("5710454") or ("5635746")		
		or ("5619051") or ("5614748") or		
		("5596214") or ("5565691") or ("5412246")		
		or ("5289030") or ("5276346") or ("5268590") or ("5254867") or ("5237188")		
		or ("5134451") or ("4954867") or		
		or ("5134451") or ("493460") or ("4814854")		
		or ("4698787") or ("3913211") or		
		("3863330") or ("3853633") or		
		("3724065")).PN.) and silicon and oxygen		
		and nitrogen and first.clm. and		
		second.clm.		
		second.cim. (((("6277708") or ("6236094") or	USPAT;	2001/10/04 13:50
-	0	("6191462") or ("6163050") or ("6133602")	US-PGPUB;	
		or ("6107657") or ("5962897") or	EPO; JPO;	
	1	("5923056") or ("5886368") or ("5838051")	DERWENT;	
		or ("5831319") or ("5828111") or	IBM TDB	
	1	("5811865") or ("5710454") or ("5635746")		
		or ("5619051") or ("5614748") or		
		("5596214") or ("5565691") or ("5412246")		
		or ("5289030") or ("5276346") or		
		("5268590") or ("5254867") or ("5237188")		
		or ("5134451") or ("4954867") or		
		("4931411") or ("4855247") or ("4814854")		
		or ("4698787") or ("3913211") or		
		("3863330") or ("3853633") or		
		("3724065")).PN.) and silicon and oxygen		
		and nitrogen and first.clm. and		
		second.clm.) and sion		
_	1	1	USPAT;	2001/10/04 14:07
	_	("6191462") or ("6163050") or ("6133602")	US-PGPUB;	1
		or ("6107657") or ("5962897") or	EPO; JPO;	
		("5923056") or ("5886368") or ("5838051")	DERWENT;	Ì
		or ("5831319") or ("5828111") or	IBM TDB	
		("5811865") or ("5710454") or ("5635746")		
	1	or ("5619051") or ("5614748") or		·
		("5596214") or ("5565691") or ("5412246")		
	İ	or ("5289030") or ("5276346") or		
		("5268590") or ("5254867") or ("5237188")		
		or ("5134451") or ("4954867") or		
		("4931411") or ("4855247") or ("4814854")		
		or ("4698787") or ("3913211") or		
1		("3863330") or ("3853633") or		
		("3724065")).PN.) and silicon and oxygen		
1		and nitrogen and first.clm. and		
		second.clm.) and silicon adj oxynitride		2001/10/04 14:40
-	0	((((("257/356") or ("257/357") or	USPAT;	2001/10/04 14.40
		("257/359") or ("257/360")).CCLS.) or	US-PGPUB;	
		((("257/410") or ("257/411") or	EPO; JPO;	
		("257/412")).CCLS.) or ((("257/632") or	DERWENT;	
		("257/635") or ("257/638") or ("257/639")	IBM TDB	
1		or ("257/649")).CCLS.)) and		
		(@rlad<19990429 or @pd<19990428)) and		1
		(silicon adj oxynitride with gate with		
		insulation) and (side adj wall adj spacer		
		with silicon with (oxide or dioxide))	USPAT;	2001/10/04 14:40
-	0	((((("257/356") or ("257/357") or	US-PGPUB;	2001/10/01 11:10
		("257/359") or ("257/360")).CCLS.) or	EPO; JPO;	
		((("257/410") or ("257/411") or	DERWENT;	
		("257/412")).CCLS.) or ((("257/632") or ("257/635") or ("257/638") or ("257/639")	IBM TDB	
		("Z5//635") OI ("Z5//636") OI (Z5//639)	1001.100	
		or ("257/649")).CCLS.)) and (@rlad<19990429 or @pd<19990428)) and		
		(silicon adj oxynitride with gate with		
		insulation) and side adj wall adj spacer		
I		THE GIACTON AND STOC GO, WALL GO, SPACEL		

		(silicon adj oxynitride with gate with	USPAT;	2001/10/04 14:59
_	0	insulation) and side adj wall adj spacer	US-PGPUB; EPO; JPO;	2001/10/01 2100
į			DERWENT; IBM TDB	
-		((silicon adj oxynitride or sion) with gate with insulation) and side adj wall adj spacer	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2001/10/04 14:41
-		((silicon adj oxynitride or sion) same gate same insulation) and side adj wall adj spacer	IBM TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/04 14:42
_	2	((((("257/356") or ("257/357") or ("257/359") or ("257/360")).CCLS.) or (("257/410") or ("257/411") or ("257/410") or ("257/410")	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2001/10/04 14:46
		("257/412")).CCLS.) or ((("257/632") or ("257/635") or ("257/638") or ("257/639") or ("257/649")).CCLS.)) and (@rlad<19990429 or @pd<19990428)) and silicon same oxy\$7 same (oxide or dioxide) same gate same ((side adj wall) near10 (silicon adj oxide or silicon adj	IBM TDB	
-	5	dioxide)) ((((("257/356") or ("257/357") or ("257/359") or ("257/360")).CCLS.) or ((("257/410") or ("257/411") or ("257/412")).CCLS.) or ((("257/632") or ("257/635") or ("257/638") or ("257/639") or ("257/649")).CCLS.)) and (@rlad<19990429 or @pd<19990428)) and silicon same oxy\$7 same (oxide or dioxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/04 14:57
-	0	same gate same side adj wall ((((("257/356") or ("257/357") or ("257/359") or ("257/360")).CCLS.) or ((("257/410") or ("257/411") or ("257/412")).CCLS.) or ((("257/632") or ("257/635") or ("257/638") or ("257/639") or ("257/649")).CCLS.)) and (@rlad<19990429 or @pd<19990428)) and (gate adj insulation adj film same "sio:n")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/04 14:57
	0	(silicon adj oxinitride with gate with insulation) and side adj wall adj spacer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/04 14:59
_	0	(silicon adj (oxynitride or oxinitride) with gate with insulation) and side adj wall adj spacer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/04 15:00
	137	((((("257/356") or ("257/357") or ("257/359") or ("257/360")).CCLS.) or ((("257/410") or ("257/411") or ("257/412")).CCLS.) or ((("257/632") or ("257/635") or ("257/638") or ("257/639") or ("257/649")).CCLS.)) and (@rlad<19990429 or @pd<19990428)) and silicon same oxy\$7 same (oxide or dioxide) same gate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/04 15:41
_	9	1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/10/04 15:53

				2224 / 2 / 2 / 2 / 3 / 5 / 5 / 5 / 5
-	2022	side adj wall near10 (silicon adj oxide or silicon adj dioxide)	USPAT; US-PGPUB;	2001/10/04 15:55
			EPO; JPO; DERWENT;	
			IBM TDB	0001 (10 (0) 15 56
-	80		USPAT; US-PGPUB;	2001/10/04 15:56
		oxide or silicon adj dioxide)	EPO; JPO;	
L			DERWENT;	
			IBM TDB	
_	89		USPAT;	2001/10/04 15:56
		or silicon adj dioxide)	US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
_	. 3		USPAT;	2001/10/04 17:56
		or silicon adj dioxide) and (silicon or	US-PGPUB;	
		polysilicon) adj gate	EPO; JPO; DERWENT;	
			IBM TDB	
_	3	5620910.pn.	USPAT;	2001/10/04 16:32
		•	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM TDB	
_	2	polysilicon adj gate.ti,ab. and (side adj	USPAT;	2001/10/04 16:46
		wall adj spacer near10 silicon adj	US-PGPUB;	
	1	dioxide)	EPO; JPO;	,
1			DERWENT; IBM TDB	
_	2	polysilicon adj gate.ti,ab. and (side adj	USPAT;	2001/10/04 16:55
		wall adj spacer near5 silicon adj dioxide)	US-PGPUB;	
			EPO; JPO;	
			DERWENT; IBM TDB	
<u> </u>	3	5620910.pn.	USPAT;	2001/10/04 17:01
_		3020310.pm.	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	12	(tungsten adj silicide near5 gate adj	USPAT;	2001/10/04 17:03
_	12	electrode) and gate adj insulation adj	US-PGPUB;	
		film	EPO; JPO;	
			DERWENT;	
		E646064 pp	IBM TDB USPAT;	2001/10/04 17:56
_	3	5646054.pn.	US-PGPUB;	2001/10/04 17:50
			EPO; JPO;	
			DERWENT;	
		(6) 23 (1) (1)	IBM TDB	2001/10/04 20:20
-	50	(field adj oxide near5 nitrogen) and (257/\$5.ccls. or 438/\$5.ccls.)	USPAT; US-PGPUB;	2001/10/04 20.20
		(23//43.0013.01 430/43.0013./	EPO; JPO;	
			DERWENT;	
			IBM TDB	